

**In the Claims:**

Please amend claims 1, 5 and 6 as set forth below in the "Listing of Claims".

**LISTING OF CLAIMS**

Claim 1 (Currently Amended): A method of cleaning a heat treatment apparatus that deposits an SiO<sub>2</sub> film by means of TEOS on an object to be processed contained in a treatment vessel capable of forming a vacuum, the method comprising the step of:

cleaning the heat treatment apparatus by supplying a mixed gas of an HF gas and an NH<sub>3</sub> gas into the treatment vessel for a period of 0.6 minute or less.

Claim 2 (Original): The method of cleaning a heat treatment apparatus according to claim 1, wherein

    during the cleaning step, a temperature in the treatment vessel is in a range of from 100°C to 300°C.

Claim 3 (Original): The method of cleaning a heat treatment apparatus according to claim 1 or 2, wherein

    during the cleaning step, a pressure in the treatment vessel is equal to or more than 53200 Pa (400 Torr).

Claim 4 (Previously Presented): The method of cleaning a heat treatment apparatus according to claim 1 or 2, wherein

    during the cleaning step, a supply amount of the HF gas is equal to or more than a supply amount of the NH<sub>3</sub> gas.

Claim 5 (Currently Amended): A method of cleaning a heat treatment apparatus that deposits an AsSG film by means of TEOS on an object to be processed contained in a treatment vessel capable of forming a vacuum, the method comprising the step of:

cleaning the heat treatment apparatus by supplying a mixed gas of an HF gas and an NH<sub>3</sub> gas into the treatment vessel for a period of 0.6 minute or less.

Claim 6 (Currently Amended): A method of cleaning a heat treatment apparatus that deposits a BSG film by means of TEOS on an object to be processed contained in a treatment vessel capable of forming a vacuum, the method comprising the step of:

cleaning the heat treatment apparatus by supplying a mixed gas of an HF gas and an NH<sub>3</sub> gas into the treatment vessel for a period of 0.6 minute or less.

Claim 7 (Previously Presented): The method of cleaning a heat treatment apparatus according to claim 3, wherein

during the cleaning step, a supply amount of the HF gas is equal to or more than a supply amount of the NH<sub>3</sub> gas.